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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO. CONFIRMATION NO.		
10/750,023	12/31/2003	Ho Lee	AB-1350 US 9344		
7590 10/11/2005			EXAMINER		
David W. Heid			LUND, JEFFRIE ROBERT		
MacPherson K	wok Chen & Heid LLP				
Suite 226			ART UNIT	PAPER NUMBER	
1762 Technology Drive			1763		
San Jose, CA 95110			DATE MAILED: 10/11/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

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		Application	No.	Applicant(s)		
Office Action Summary		10/750,023		LEE, HO		
		Examiner		Art Unit		_
		Jeffrie R. Lu	nd	1763		
 Period for	The MAILING DATE of this communication Reply	appears on the c	over sheet with the c	orrespondence add	iress	_
A SHO WHICI - Extens after S - If NO p - Failure Any re	PRTENED STATUTORY PERIOD FOR REHEVER IS LONGER, FROM THE MAILING ions of time may be available under the provisions of 37 CF IX (6) MONTHS from the mailing date of this communication veriod for reply is specified above, the maximum statutory period for reply within the set or extended period for reply will, by so ply received by the Office later than three months after the replace in the patent term adjustment. See 37 CFR 1.704(b).	G DATE OF THIS  R 1.136(a). In no event  n.  eriod will apply and will e  statute, cause the applica	COMMUNICATION however, may a reply be tim xpire SIX (6) MONTHS from tion to become ABANDONE	N. nely filed the mailing date of this col D (35 U.S.C. § 133).		
Status						
2a)⊠ 3 3)□ 3	Responsive to communication(s) filed on 2 This action is <b>FINAL</b> . 2b) Since this application is in condition for all closed in accordance with the practice unc	This action is nor owance except for	r formal matters, pro		merits is	
	on of Claims					
4)   4 5)   6 6)   6 7)   6 8)   6 Application 10)   7	Claim(s) 1-12 is/are pending in the applicate a) Of the above claim(s) is/are with Claim(s) is/are allowed. Claim(s) 1-12 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction as	ndrawn from consind/or election required is/are: a) according to the drawing(s) be prection is required	uirement. epted or b)⊡ object held in abeyance. See if the drawing(s) is obj	e 37 CFR 1.85(a). jected to. See 37 CF	R 1.121(d).	
12)⊠ A a)⊠ 2	Acknowledgment is made of a claim for form the common of the priority documed in the priority documed	nents have been nents have been priority documen ureau (PCT Rule	received. received in Applicati ts have been receive 17.2(a)).	on No ed in this National \$	Stage	
2) 🔲 Notice 3) 🔯 Inform	s) of References Cited (PTO-892) of Draftsperson's Patent Drawing Review (PTO-948 ation Disclosure Statement(s) (PTO-1449 or PTO/SE No(s)/Mail Date 2/05, ( JoS.	5) 3/08) 5	)  Interview Summary Paper No(s)/Mail Da )  Notice of Informal P )  Other:	ate	-152)	

#### **DETAILED ACTION**

## Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 2. Claims 1-9 and 11 are rejected under 35 U.S.C. 102(b) as being anticipated by Zhao et al, US Patent 5,558,717.

Zhao et al teaches a CVD apparatus that includes: a processing chamber 134 with an inner space 141; a gas feed member 126 for supplying a gas into the chamber; an aluminum diffuser 122 partitioning the inner space of the chamber into a first and second partitions having a plurality of holes 121 and includes an "L" shaped extension overlapping a surface of the insulating frame (area surrounding O-ring 125) 120, the ceramic insulating frame 120 disposed in between the chamber and the diffuser, and located on the lower surface of the "L" shaped extension; a baffle plate (blocking plate) 124 for mixing and spreading the gas feed member before passing through the holes of the diffuser; and an RF source connected to the diffuser and the pedestal is grounded. (Entire document, specifically Figure 1) The specific substrate processed is an intended use of the apparatus and the apparatus of Zhao et al can inherently process any desired substrate.

3. Claims 1, 2, 4-9, and 11 are rejected under 35 U.S.C. 102(b) as being anticipated by Koai et al, US Patent 6,106,625.

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Koai et al teaches a CVD apparatus that includes: a processing chamber 150 with an inner space 26; a gas feed member 160 for supplying a gas into the chamber; a diffuser 156 partitioning the inner space of the chamber into a first and second partitions having a plurality of holes 180 and includes an "L" shaped extension 158 overlapping a surface of the insulating frame 174, the ceramic insulating frame 174 disposed in between the chamber and the diffuser, and located on the lower surface of the "L" shaped extension; a baffle plate (blocking plate) 30 for mixing and spreading the gas feed member before passing through the holes of the diffuser; and an RF source connected to the diffuser and the pedestal is grounded. (Entire document, specifically Figure 8) The specific substrate processed is an intended use of the apparatus and the apparatus of Koai et al can inherently process any desired substrate.

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4. Claims 1, 2, 4-6, and 8-13 are rejected under 35 U.S.C. 102(b) as being anticipated by Leusink et al, US Patent 6,302,057 B1.

Leusink et al teaches a CVD apparatus that includes: a processing chamber 10 with an inner space 15; a gas feed member 65 for supplying a gas into the chamber; a metal diffuser 20 partitioning the inner space of the chamber into a first and second partitions having a plurality of holes 21 and includes an "L" shaped extension 54 overlapping a surface 52 of the ceramic insulating frame 120, the ceramic insulating frame 120 disposed in between the chamber and the diffuser, and located on the surface of the "L" shaped extension and facing the surface of the substrate; and an RF source 24 connected to the diffuser 20 and the pedestal is grounded. (Entire document, specifically Figure 1) The specific substrate processed is an intended use of the

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apparatus and the apparatus of Leusink et al can inherently process any desired substrate.

### Claim Rejections - 35 USC § 103

- 5. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 6. Claims 3 and 7 are rejected under 35 U.S.C. 103(a) as being unpatentable over Leusink et al, US Patent 6,302,057, in view of Zhao et al, US Patent 5,558,717.

Leusink et al was discussed above.

Leusink et al differs from the present invention in that Leusink et al does not teach that the diffuser 20 is stainless steel or aluminum, and a baffle plate.

Zhao et al teaches an aluminum diffuser plate and a baffle plate as discussed above.

The motivation for making the diffuser of Leusink et al out of aluminum as taught by Zhao et al is to provide a specific metal as required by Leusink et al but only generically described. The motivation for adding a baffle plate to the showerhead of Leusink et al is to more uniformly distribute the gas supplied to the diffuser of Leusink et al as taught by Zhao et al.

Therefore it would have been obvious to one of ordinary skill in the art at the time the invention was made to make the diffuser of Leusink et al out of aluminum and add a diffuser as taught by Zhao et al.

## Response to Arguments

7. Applicant's arguments filed June 29, 2005 have been fully considered but they are not persuasive.

In regard to the argument that Zhao et al and Koai et al teaches that the insulator under the extension and not on the extension, the Examiner disagrees. "On" is a very broad word and includes "on" the lower side of the extension. Thus, the insulators of Zhao et al and Koai et al are "on" the extensions.

#### Conclusion

- 8. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. The cited art teaches the technological background of the invention.
- 9. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of

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the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

10. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Jeffrie R. Lund whose telephone number is (571) 272-1437. The examiner can normally be reached on Monday-Thursday (6:30 am-6:00pm).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on (571) 272-1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Jeffrie R. Lund Primary Examiner Art Unit 1763

JRL 9/10/05